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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	11-14800	Jan. 22, 1999	JAPAN (with English abstract)	—	—		
	0 903 638	Mar. 24, 1999	EUROPEAN	—	—		
	55-71311	May 16, 1980	JAPAN (with partial English translation)	—	—		
	10-172883	June 26, 1998	JAPAN (with English abstract)	—	—		
	9-218299	Aug. 19, 1997	JAPAN (with English abstract)	—	—		

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	"Modeling X-ray proximity lithography", Jerry Z. Y. Guo et al., Journal of Research and Development, Vol. 37, No. 3, may 1993, pp. 331-349
	"Updated system model for x-ray lithography", M. Khan et al., J. Vac. Sci. Technol. B 12(6), Nov/Dec 1994, pp. 3930-3935
	"50-nm x-ray lithography using synchrotron radiation", Y. Chen et al., J. Vac. Sci. Technol. B 12(6), Nov/Dec 1994, pp. 3959-3964
	NTT R&D Vol. 43, No. 6, p. 501 (1994)

EXAMINER: _____ DATE CONSIDERED: 7/11/01

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